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		438/637	Method for fabricating semiconductor device	111	20010628	05 20010005626 A1		9
		257/296	SEMICONDUCTOR DEVICE AND METHOD OF FABRICATING THE SAME	71	20010906			8
		438/637	T H	21	20020228	US 20020025669 A1		7
		257/296	SEMICONDUCTOR MEMORY DEVICE USING DOUBLE LAYERED CAPPINGPATTERN AND SEMICONDUCTOR MEMORY DEVICE FORMED THEREBY	37	20020613	US 20020070398 A1		
		438/612	: -	10	20020815	US 20020111006 A1		σ [
		257/288	Semiconductor device and its manufacture	38	20021003	US 20020140008 A1		4
	257/316; 438/201; 438/257; 438/626; 438/627	257/315	Metal local interconnect self-aligned source flash cell	H H	20030116	US 20030011023 A1		ω
	8	438/257	Optimized flash memory cell	11	20030116	US 20030013253 A1		2
		600/508	Medical testing system with an illuminating component and automatic shut-off	12	20030130	US 20030023174 A1		П
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10		⊠	US B2	6534375	20030318	150	METHOD OF FORMING A CAPACITOR IN A SEMICONDUCTOR INTEGRATED CIRCUIT DEVICE USING A METAL SILICON NITRIDE LAYER TO PROTECT AN UNDERLYING METAL SILICIDE LAYER FROM OXIDATION DURING SUBSEQUENT PROCESSING STEPS	438/386	438/387; 438/399; 438/683; 438/686; 438/785	
11		⊠	US B2	6465310	20021015	œ	Methods of forming self-aligned contact pads on electrically conductive lines	438/299	438/229	
12		⊠	US B1	6461923	20021008	10	Sidewall spacer etch process for improved silicide formation	438/305	438/586; 438/680	
13		⋈	US B1	6437411	20020820	ω Մ	Semiconductor device having chamfered silicide layer and method for manufacturing the same	257/413	257/316	
14		⊠	US B1	6432816	20020813	10	Method for fabricating semiconductor device	438/637	438/299	
15		⊠	US B1	6417097	20020709	21	Methods of forming a contact structure in a semiconductor device	438/637	438/773; 438/783	
16		⊠	US B1	6352896	20020305	29	Method of manufacturing DRAM capacitor	438/253	438/396; 438/672; 438/675	
17		Ø	US B1	6350650	20020226	22	Method for fabricating a semiconductor memory device	438/256	8/2	
18		☒	US B1	6342416	20020129	28	Method of manufacturing a semiconductor memory device	438/239	438/238; 438/626; 438/761	

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20	Kajiyama, Takeshi	⊠							US	6271081	
21	Lee, Joo-Young et al.	⊠							US	6248654	ф
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